

U. S. PATENT DOCUMENTS

<u>Examiner Initial</u>	<u>Document Number</u>	<u>Issue Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Filing Date If Appropriate</u>
<i>Aud</i>	6,006,694	12/28/99	DeOrnellas et al.	118	723 I	



FOREIGN PATENT DOCUMENTS

<u>Examiner Initial</u>	<u>Document Number</u>	<u>Publication Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Translation If Appropriate</u>
<i>Aud</i>	EP 0421348	04/10/91	Tamura et al.	C23C	14/35	
<i>Aud</i>	EP 0650182	04/26/95	Rice et al.	H01J	37/32	
<i>Aud</i>	EP 0727807	08/21/96	Hanawa et al.	H01J	37/32	
<i>Aud</i>	EP 0732729	09/18/96	Kanai et al.*	H01J	37/32	
<i>Aud</i>	EP 0838841	04/29/98	Schneider et al.	H01J	37/32	
<i>Aud</i>	JP 07221070	08/18/95	Kadomuro Shingo	H01L	21/3065	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

Aud Lee et al., "Patterning of Pt thin films using SiO₂ mask in a high density plasma", *J. Kor. Inst. Telematics & Elect.*, Vol.34D, No.3, pp.187 - 192 (1997).

Aud Lieberman et al., "Plasma Sources for Thin Film Deposition and Etching", Physics of Thin Films: Advances in Research and Development, Vol. 18, Maurice H. Francombe and John L. Vossen, eds., Academic Press, Inc., San Diego, pp. 10-13, 30, 31, 52, 53, 60, 61 (1994).

Alla c Ola
Examiner

5/27/2003
Date Considered

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

* Cited by the Examiner in the parent application.

FORM PTO-1449
(Equivalent)

U.S. Department of Commerce
Patent and Trademark Office

U.S. Application Serial No.

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AM-2090P1.C1/2090.C2

INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

(Use several sheets if necessary)

Jeng H. Hwang et al.
Applicants

June 29, 2001
Filing Date

1763
Group

U. S. PATENT DOCUMENTS

Examiner Initial	Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
<u>Auo</u>	5,110,408	05/05/92	Fujii et al.	156	643	
	5,419,029	05/30/95	Raaijmakers	29	447	
	5,569,363	10/29/96	Bayer et al.	204	192.32	
	5,599,403	02/04/97	Kariya et al.	136	258	
	5,614,055	03/25/97	Fairbairn et al.	156	345	
	5,641,375	06/24/97	Nitescu et al.	156	345	
	5,685,941	11/11/97	Forster er al.	156	345	
	5,686,339	11/11/97	Lee et al.*	437	52	
	5,753,044	05/19/98	Hanawa et al.	118	723 I	
	5,763,851	06/09/98	Forster et al.*	219	121.43	
	5,800,688	09/01/98	Lantsman et al.	204	298.11	
<u>Auo</u>	5,837,057	11/17/98	Koyama et al.	118	723 VE	

Allen C. Oden
Examiner

5/27/2003
Date Considered

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